



U.S. S.N. 10/050,322

1756  
10/3/03  
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Tsai et al.

Group Art Unit: 1756

Serial No.: 10/050,322

Examiner: N. M. Barreca

Filed: 01/15/2002

In Response to Office Action

Dated: 06/23/2003

**RECEIVED**

For: A BI-LAYER PHOTORESIST DRY DEVELOPMENT AND  
REACTIVE ION ETCH METHOD

SEP 29 2003

TC 1700

Attorney Docket No.: 67,200-613

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I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, Va 22313-1450

Date:

Sept. 23/03

Kathy Bixon

RESPONSE TO OFFICE ACTION

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Va 22313-1450

Dear Sir:

In response to an Office Action mailed 06/23  
/2003, please enter the following amendments and consider the  
following remarks.

10/06/2003 CS1A61  
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